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said raster element of said first mirror or lens is imaged in said reticule plane by said raster element of said second mirror or lens;

an image of said raster element of said first mirror or lens is partially superimposed in said reticule plane; and

said secondary light source is imaged in an exit pupil by said optical element.

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104. Process for the production of microelectronic components according to claim ~~53~~ 53.

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105. The illumination system according to claim ~~62~~ 62, wherein said light source is a plasma focus source.

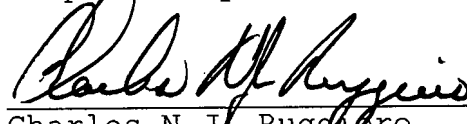
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106. The illumination system according to claim ~~63~~ 63, wherein said light source is a pinch-plasma source.

REMARKS

New claims 53 through 106 are added to properly protect the full scope of the invention.

Respectfully submitted,

May 4, 1999
Date



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